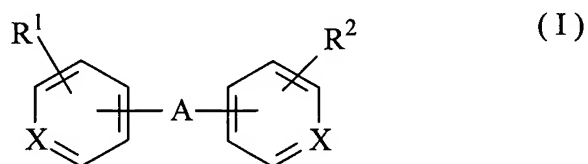


AMENDMENT TO THE ABSTRACT

A negative type resist composition is provided, which provides excellent resolution, satisfactory profile and outstanding process stability: is suitable for exposure using deep ultra violet ray; and comprises alkali soluble resin, acid generator, crosslinking agent, and a basic compound represented by the following formula (I)



wherein, A represents sulfide group, disulfide group or bivalent aliphatic hydrocarbon residue which may be optionally interrupted by imino group, [ sulfide group, or disulfide group,] X represents nitrogen atom or C(NH<sub>2</sub>), and R<sup>1</sup> and R<sup>2</sup> independently represent hydrogen or alkyl.